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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Not for submission under 37 CFR 1.99)

Application Number		10549356		
Filing Date		2007-02-15		
First Named Inventor Baike		rikar et al.		
Art Unit		1792		
Examiner Name Fletch		ner III, William P		
Attorney Docket Number		62657A		

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INFORMATION DISCLOSURE		Filing Date			2007-02-15					
		First Named Inventor Baike			erikar et al.					
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					nit			1792				
(NOT IOF :	submi	ission under 37 CFR 1	.99)	Examiner Name Fletch			her III, William P					
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Standard ST.3	3). ³ Fo	USPTO Patent Documents at www.US or Japanese patent documents, the indicated by the appropriate symbols as indicated	ication of the year of the reign	of the E	imperor must precede the s	serial number of the patent do	cument.		

English language translation is attached.